

**THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant(s): Udo Dinger et al.  
Serial No.: 10/779,516  
For: A SUBSTRATE MATERIAL FOR X-RAY OPTICAL COMPONENTS  
Filed: February 13, 2004  
Examiner: Not Yet Assigned  
Art Unit: 2878  
Confirmation No.: 8909  
Customer No.: 27623

Attorney Docket No.: 637.0033USX

Date: June 9, 2004

**INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In accordance with applicants' duty of disclosure under 37 C.F.R. §1.56, we are enclosing form PTO-1449 listing information that may be material to the patentability of this application.

Pursuant to the waiving of the requirement of 37 CFR 1.98 (a)(2)(i), copies of the U.S. references cited in the attached form PTO-1449 are not enclosed.

It is applicants' belief that none of the citations described in the enclosed PTO-1449 are that which is claimed in the present invention.



It should be understood that attention has been called to the citations that have been deemed to be pertinent to the claimed present invention. In concluding what was pertinent, the criteria employed was considered most appropriate in light of the invention shown in the present application. However, the Examiner or others may deem some other criteria to be just as appropriate or more appropriate. Therefore, the Examiner is respectfully urged to review the listed citations and to make the usual careful independent search for other prior art that may be pertinent.

Since this Information Disclosure Statement is being filed prior to the issuance of the first Office Action based on the merits, no petition or fee is required.

Applicants respectfully request favorable consideration and that this application be passed to allowance.

Respectfully submitted,

A handwritten signature in black ink, appearing to read "Charles N. J. Ruggiero".

Charles N. J. Ruggiero

Reg. No. 28,468

Attorney for Applicant(s)

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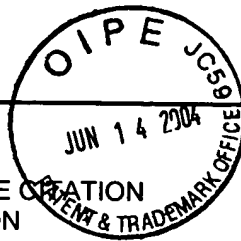
CUSTOMER NO.: 27623

Sheet 1 of 1

FORM PTO-1449

INFORMATION DISCLOSURE CITATION  
IN AN APPLICATION

(Use several sheets if necessary)



Docket Number (Optional)

637.0033USX

Application Number

10/779,516

Applicant

Udo Dinger et al.

Filing Date

February 13, 2004

Group Art Unit

2878

## U. S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	2001/0028518	10/11/01	Kaiser	359	883	
	2002/0114089	8/22/02	Dinger et al.	359	853	
	D322,813	12/31/91	Wilson	D19	88	
	2,326,059	8/3/43	Nordberg	106	52	
	5,070,045	12/3/91	Comte et al.	501	4	
	5,591,682	1/7/97	Goto	501	4	
	6,198,793	3/6/01	Schultz et al.	378	34	
	6,244,717	6/12/01	Dinger	359	859	
	6,377,655	4/23/02	Murakami et al.	378	84	

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						YES	NO
	0 955 565 A2	11/10/99	Europe			X	
	198 30 449 A1	1/27/00	Germany				X
	199 03 807 A1	11/11/99	Germany				X
	199 07 038 A1	8/31/00	Germany				X
	199 23 609 A1	12/2/99	Germany				X
	04367538 A	12/18/92	Japan			X	
	2000247681 A	9/12/00	Japan			X	

## OTHER DOCUMENTS (including Author, Title, Date, Pertinent Pages, Etc.)

	XP-000991487 Mask Substrate Requirements and Development for Extreme Ultraviolet Lithography (EUVL), by Tong et al., and Lawrence Livermore Nat'l Lab., Motorola, and Intel Corp., (9/99), SPIE Vol. 3873, pgs 421-428.
	XP-008012782 Experiences in the Precision Machining of Grazing Incidence X-Ray Mirror Substrates, by McKeown et al., from Cranfield Unit for Precision Engineering and Cranfield Institute of Technology, (1985), SPIE Vol. 571, Large Optics Technology, pgs 42-50
	Mirror Substrates for EUV-Lithography: Progress in Metrology and Optical Fabrication Technology, by Dinger et al., (2000), SPIE Vol. 4146, pgs 35-46

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP §609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the applicant.